

	Hits	Search Text	DBs
6	114	((resist or photoresist) same pattern) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
7	10	((resist or photoresist) same pattern) and ((striation or roughness or variation or var\$4) same (resist or photoresist) same (pattern or via or hole) same uneven\$5) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
8	54	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth\$4 or cover\$4 or thicken\$5 or enhanc\$4) same (coat\$4 or layer or film)) and etch\$4 and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
9	0	((resist or photoresist) same pattern) and etch\$4 and uniformit\$4 and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI same VLSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
10	42	((resist or photoresist) same pattern) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI) and ((aspect near7 ratio) near20 (VLSI or LSI))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	1	((resist or photoresist) same pattern) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI same VLSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
13	21	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth\$4 or cover\$4 or thicken\$5 or enhanc\$4 or improv\$4) same (coat\$4 or layer or film)) and (resin same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
14	25	((resist or photoresist) same pattern) and ((resist or photoresist) near16 (coat\$4 or layer or film)) and (resin same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
15	4	S14 NOT S13	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
16	25	((resist or photoresist) same pattern) and (resin same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
17	25	((resist or photoresist) same pattern) and (resin\$4 same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
18	32	((resist or photoresist)) and (resin\$4 same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
19	11	S18 NOT S13	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
20	50	((resist or photoresist)) and (resin\$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
21	29	S20 NOT S13	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB